

REMARKS

Applicant has rewritten claims 1 and 7.

The Examiner stated, (Office Action, page 2), in connection with the translation of a Japanese Office Action dated December 10, 2002 submitted with an Information Disclosure Statement (IDS) filed herein on January 13, 2003, that this reference was not listed in the Information Disclosure Statement (IDS) and, accordingly, has not been considered. In response, Applicant states that this translation was not submitted as a reference, but rather to fulfill the requirement of a concise statement of the relevance of Japanese Patent Publication No. 06-163590, a non-English language reference, see 37 C.F.R. §1.98(a)(3)(i) and Manual of Patent Examining Procedure (M.P.E.P.), p. 600-122.

Claims 1, 4, 6, 7, and 8 were rejected under 35 U.S.C. §112, first paragraph. Claims 1 and 7 were rewritten to overcome this rejection.

Claims 1, 4, 6, 7 and 8 were rejected under 35 U.S.C. §103(a) as being unpatentable over the article Im et al., "Single-crystal Si films for thin-film transistor devices," Applied Physics Letters 70 (25) 23 June 1997, pp. 3434-3436 in view of Hennings, U.S. Patent No. 3,712,740, and Makita, U.S. Patent No. 5,821,562.

Independent claims 1 and 7 provide that an alignment mark corresponding to an alignment mark pattern on the optical mask is formed by the irradiation of the desired portion of the second-property or amorphous semiconductor film with the laser light through the optical mask to change the irradiated portion of the desired portion of the second-property or amorphous semiconductor film to the first-property or crystalline semiconductor film. This feature is supported in the specification by, for example, page 32, lines 6-16, and in the drawings by, for example, Figs. 12A-12B.

This feature is nowhere disclosed, taught or suggested by Im et al., Hennings or Makita singly or in combination. In Im et al., there is no disclosure at all of alignment mark patterns or alignment marks. With regard to Hennings, although the use of register marks to bring two articles into alignment is disclosed, (Abstract), it is nowhere disclosed, taught, or suggested that the laser light irradiating and changing the property of a semiconductor film also forms by irradiation an alignment mark, as claimed herein.

In Makita, the boundaries of alignment mark regions in which catalyst elements are introduced are made clearer by irradiation of a laser light which causes a roughened surface, the irradiation being done without a mask, (column 27, lines 13-28). However, as claimed in claims 1 and 7 herein, the irradiation forming the alignment mark is done through an optical mask.

In addition, Makita uses laser irradiation to make the distinction between a catalyst-introduced region and the other region. According to the present invention, however, an alignment function is provided through the use of a difference in optical characteristic between a laser-irradiated region and a non-irradiated region.

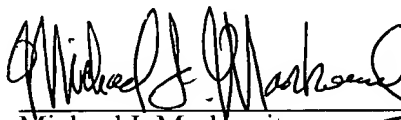
CONCLUSION

An earnest effort has been made to be fully responsive to the Examiner's objections. In view of the above amendments and remarks, it is believed that independent claims 1 and 7 are in condition for allowance, as well as the claims dependent therefrom. Passage of this case to allowance is earnestly solicited.

However, if for any reason the Examiner should consider this application not to be in condition for allowance, he is respectfully requested to telephone the undersigned attorney at the number listed below prior to issuing a further Action.

Any fee due with this paper, not fully covered by an enclosed check, may be charged on Deposit Account 50-1290.

Respectfully submitted,

A handwritten signature in black ink, appearing to read "Michael I. Markowitz", is written over a horizontal line.

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